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(54) **LIQUID CRYSTAL DISPLAY DEVICE AND
FABRICATION METHOD OF A
CONDUCTIVE SUBSTRATE**

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G02F 1/1333 (2006.01)
H01L 33/42 (2010.01)
G02F 1/1337 (2006.01)

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(2013.01); **G02F 1/133707** (2013.01); **G02F**
1/136286 (2013.01); **H01L 33/42** (2013.01)

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27/3244; H01L 27/3248; H01L 29/4908;
H01L 29/78669; H01L 29/78678; H01L
2227/323; H01L 21/32139; H01L 21/77;
H01L 21/0272; H01L 21/0273; H01L 21/266;
H01L 21/283; H01L 21/31111; H01L
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H01L 21/467; H01L 21/47; H01L 21/4885;
H01L 21/707; H01L 21/76805; H01L
21/76838; H01L 21/76877; H01L 51/102;
H01L 51/107; H01L 51/0017; H01L 51/0021;
H01L 51/5203; G02F 1/136286; G02F 1/1368;
G02F 1/1362; G02F 1/136227; G02F
1/134336; G02F 1/133345; G02F 1/134309;
G02F 1/1345; G02F 1/136209; G02F
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2001/16329; G02F 2001/136295; G06F
2203/04103; G09G 2300/0426; G09G
2310/0205; G09G 3/3659; G09G 3/3677;
G09G 3/3688

USPC 257/72, 59; 438/158, 151, 587, 675;
349/43, 46, 138, 139, 42, 187, 141
See application file for complete search history.

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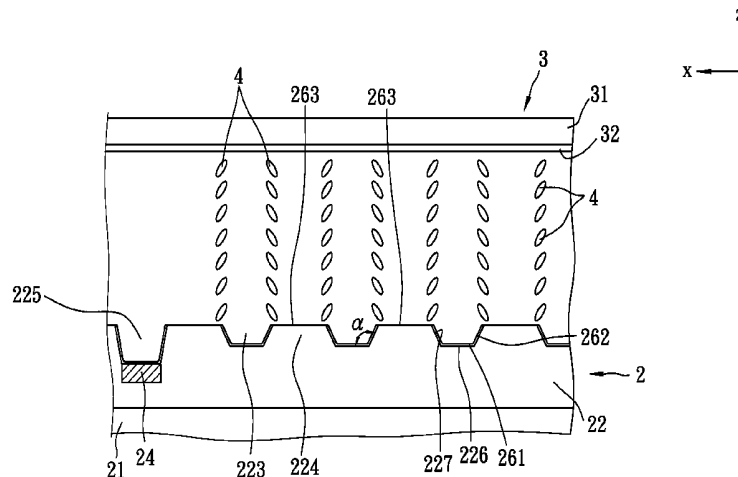
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(57) **ABSTRACT**

A liquid crystal display device includes: a first substrate; a second substrate spaced apart from the first substrate; and a plurality of liquid crystal molecules disposed between the first and second substrates. The first substrate includes a transparent substrate, an insulator layer formed on a surface of the transparent substrate and formed with a plurality of grooves, and a pixel electrode formed on a surface of the insulator layer and formed with a plurality of electrode slits.

4 Claims, 13 Drawing Sheets



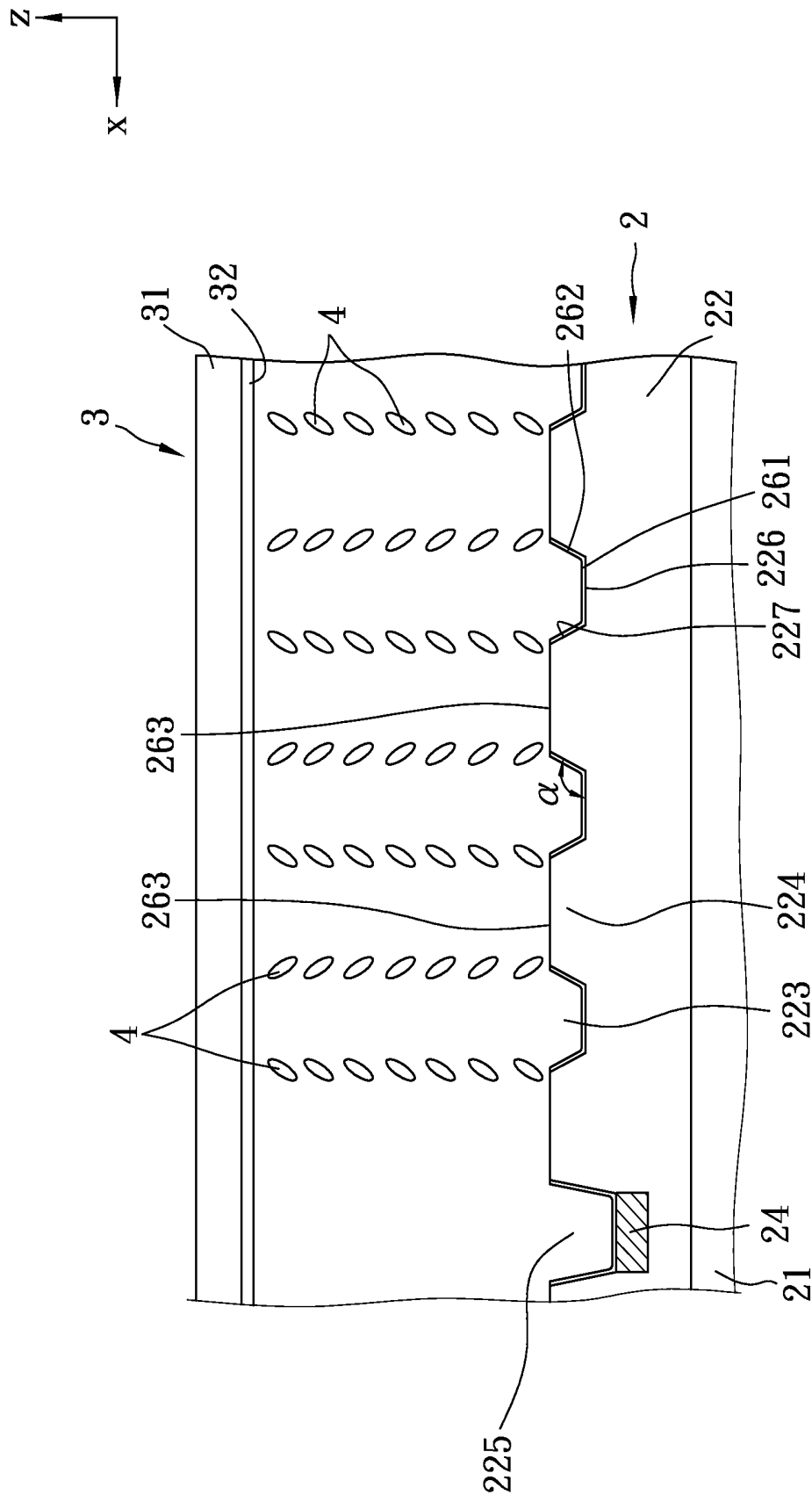


FIG. 1

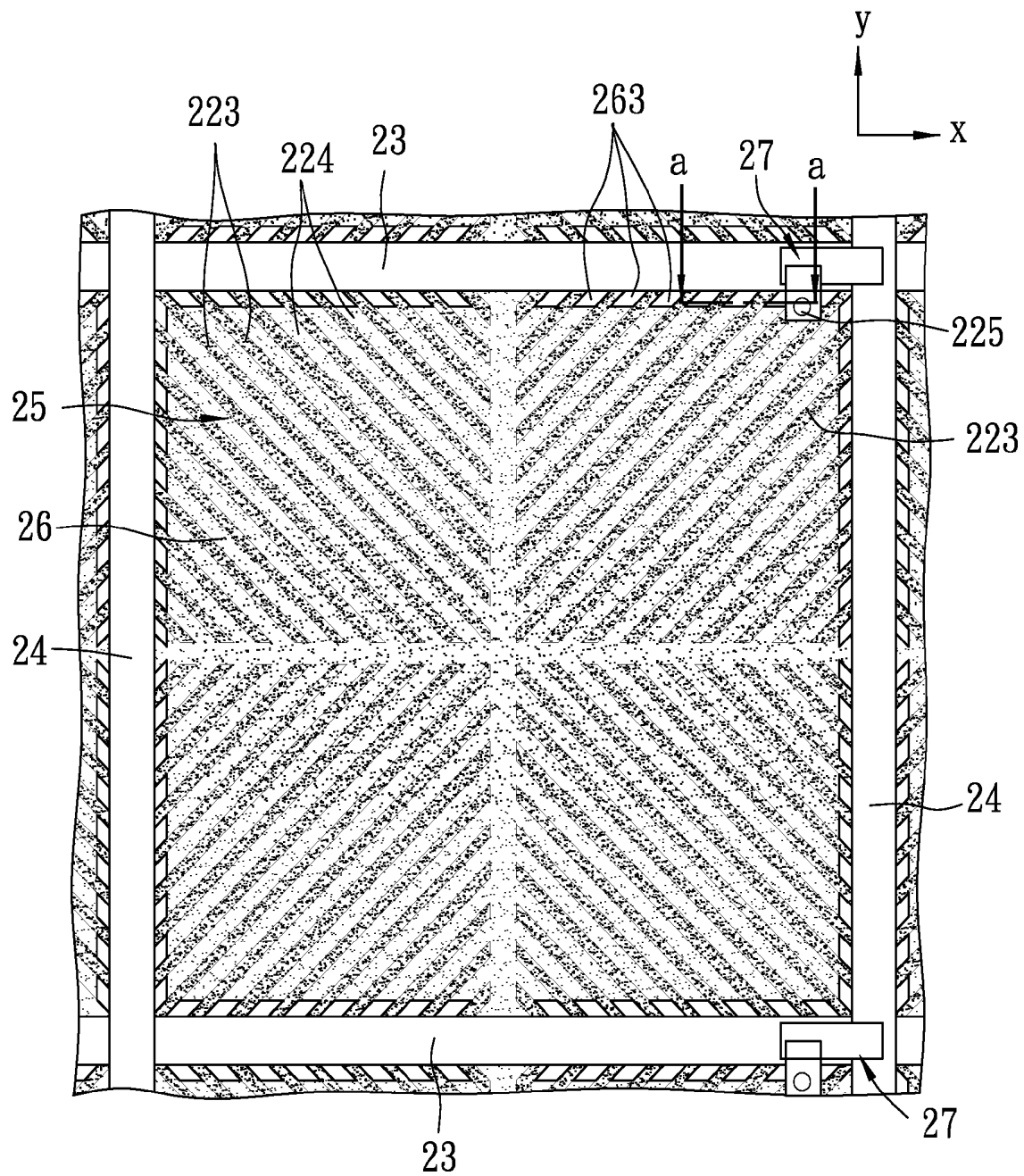


FIG. 2

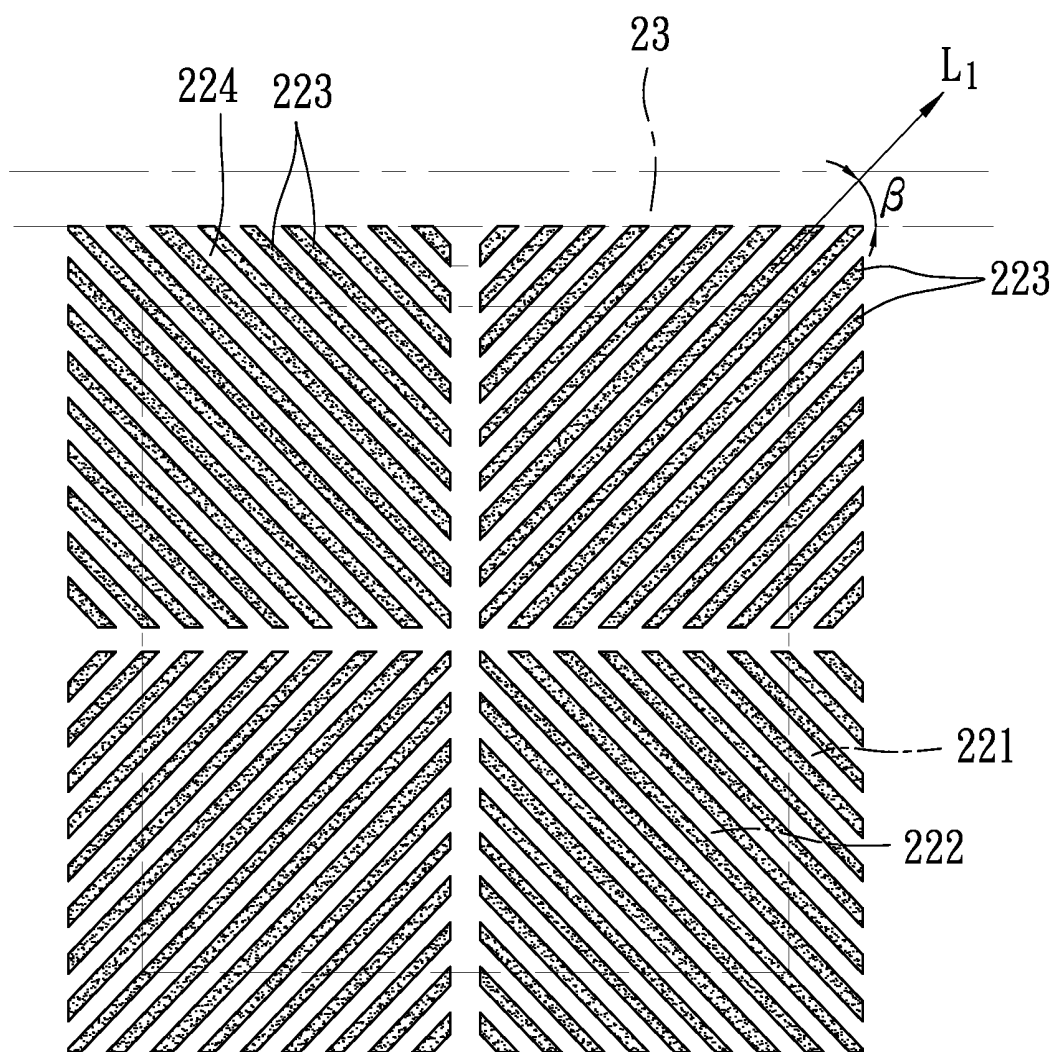


FIG. 3

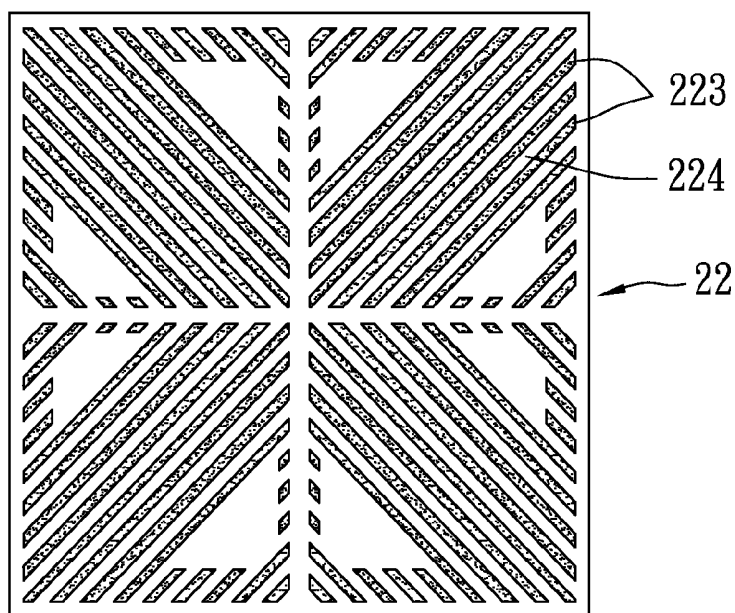


FIG. 4

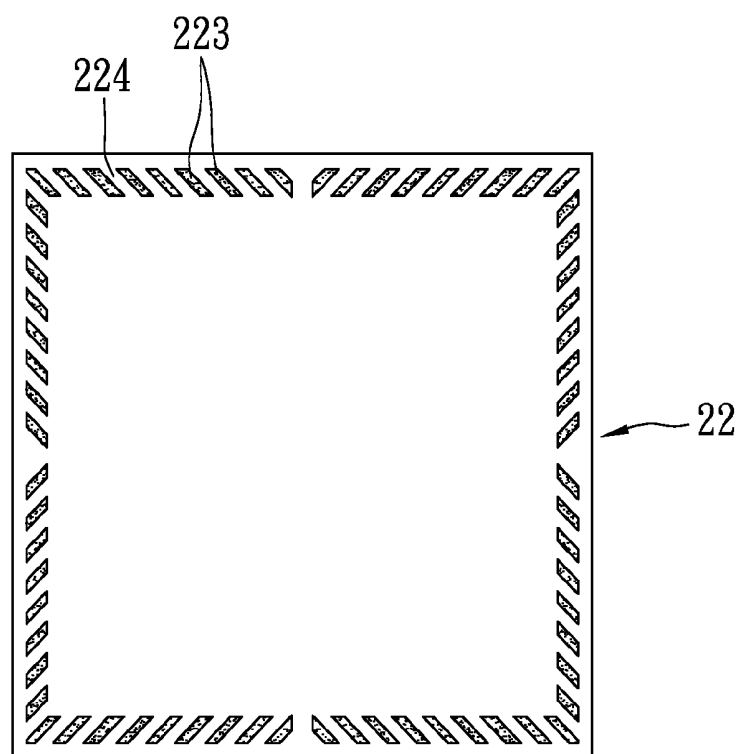


FIG. 5

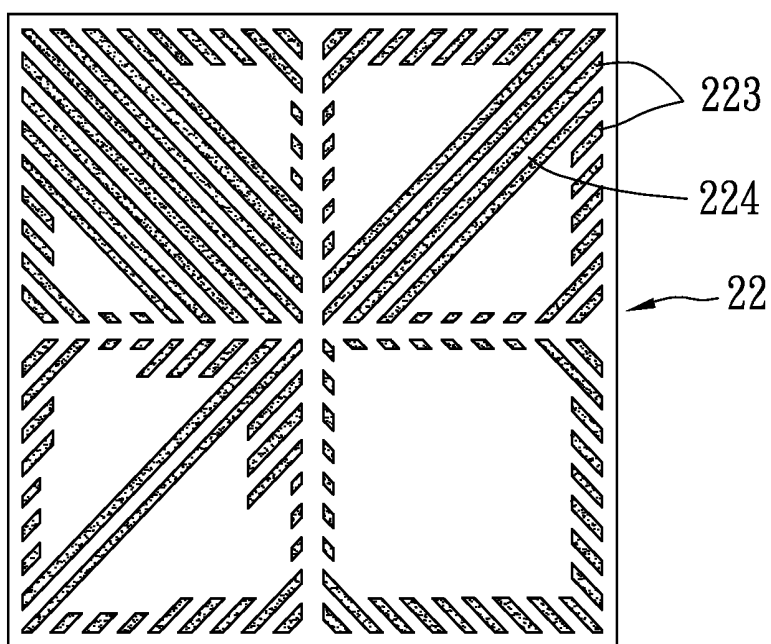


FIG. 6

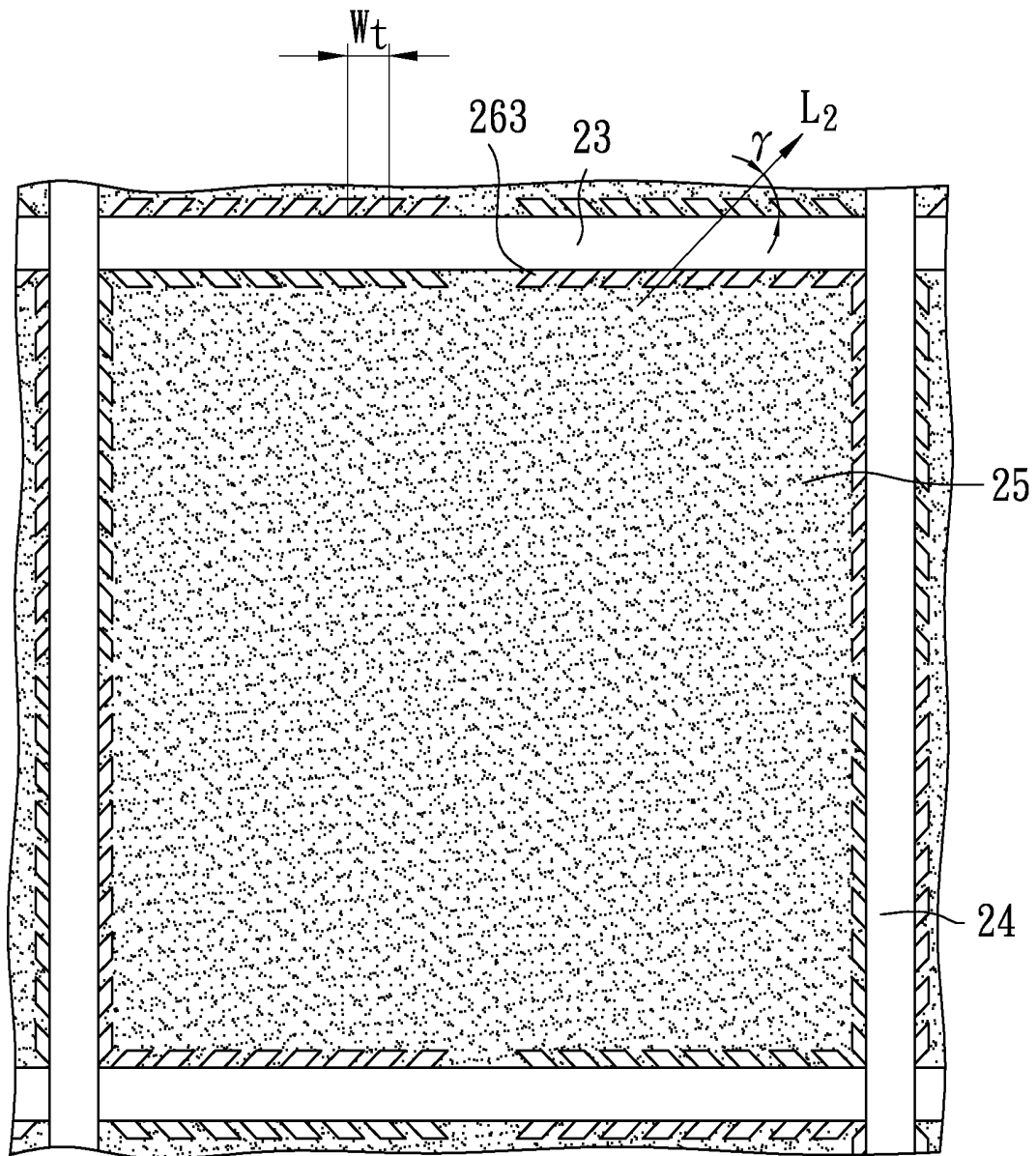


FIG. 7

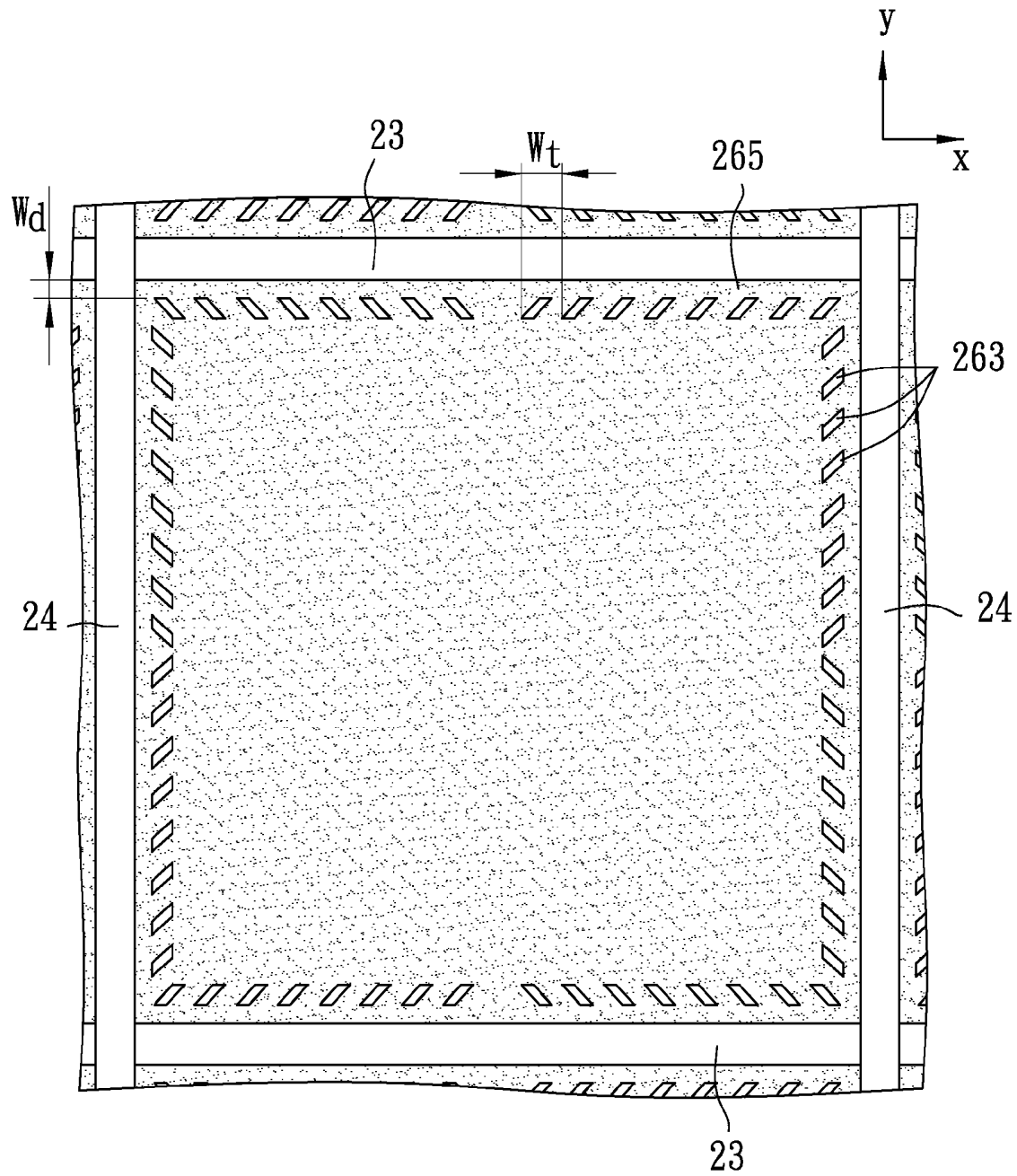


FIG. 8

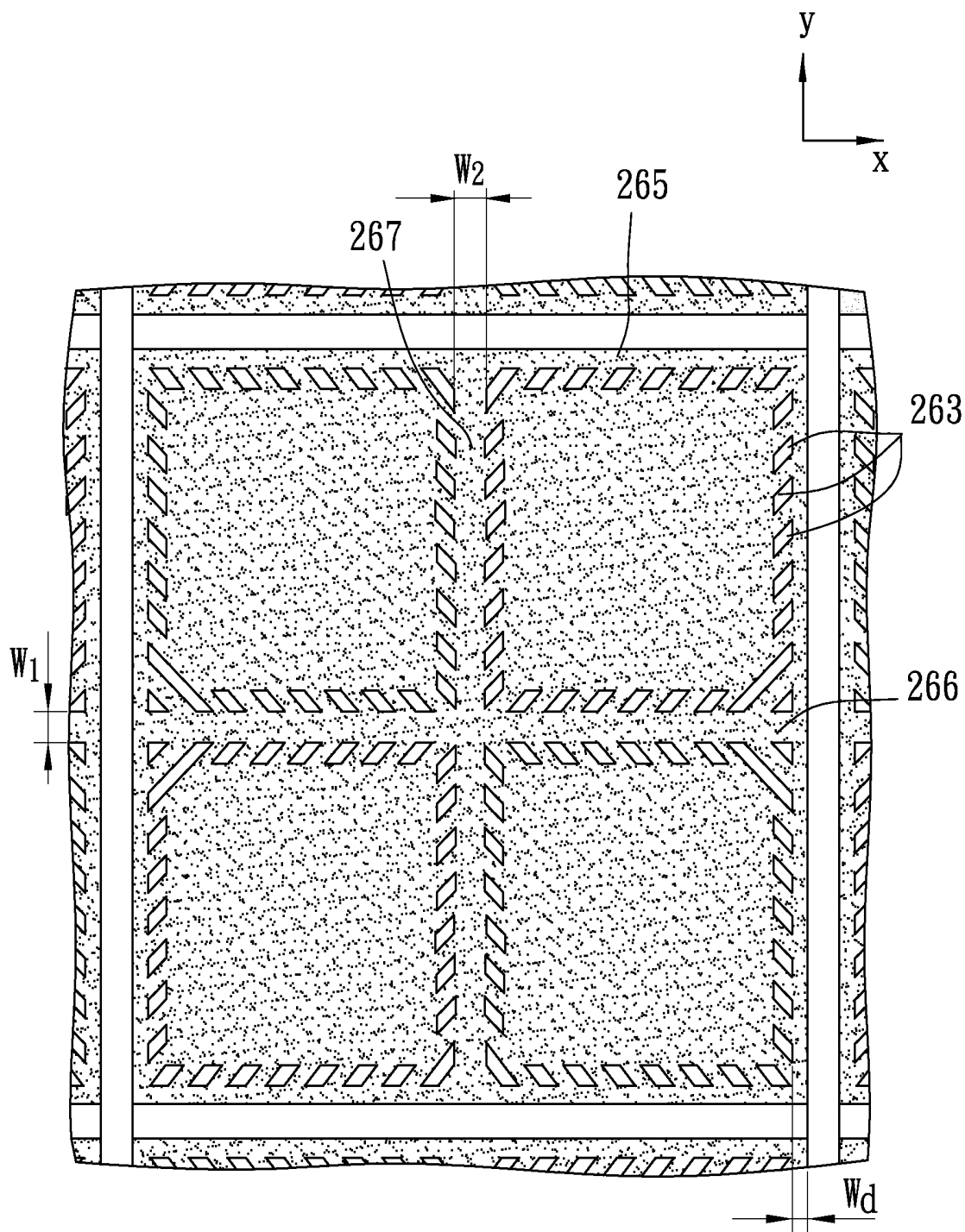


FIG. 9

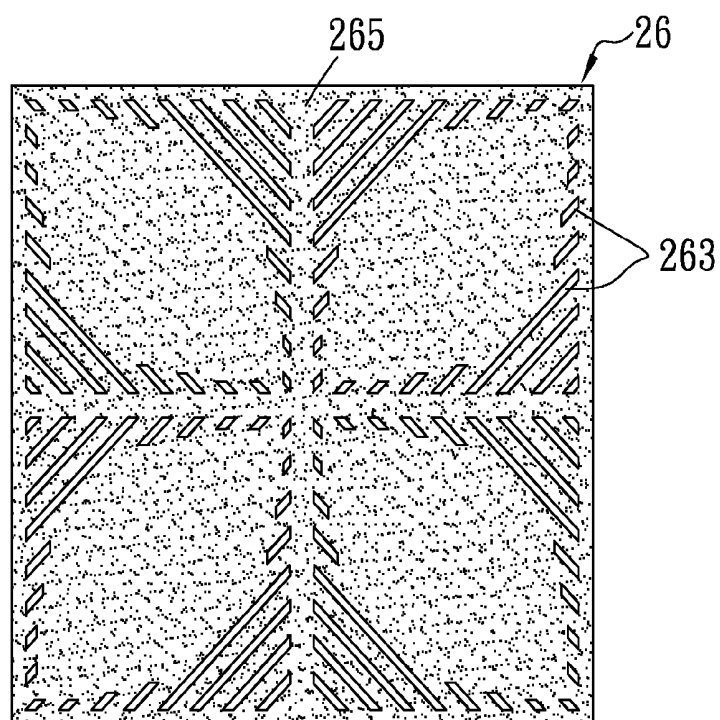


FIG. 10

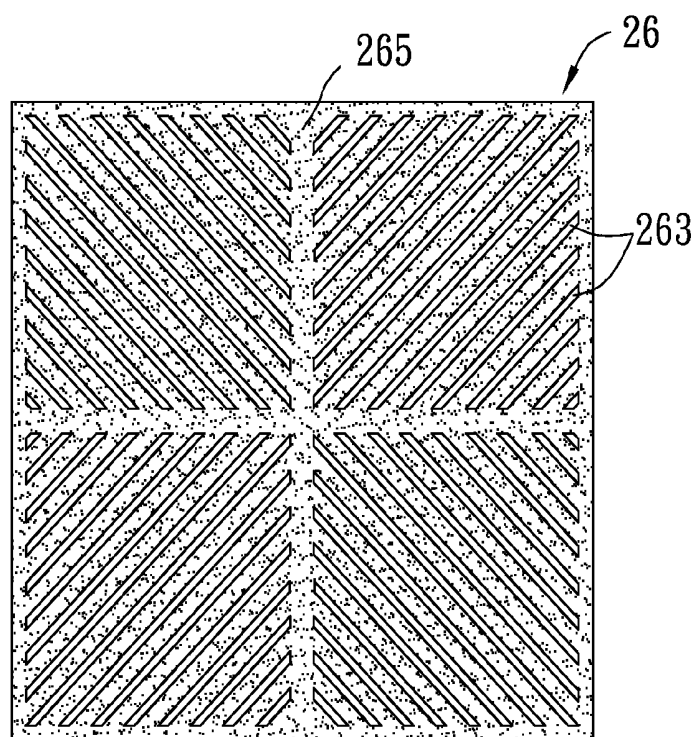


FIG. 11

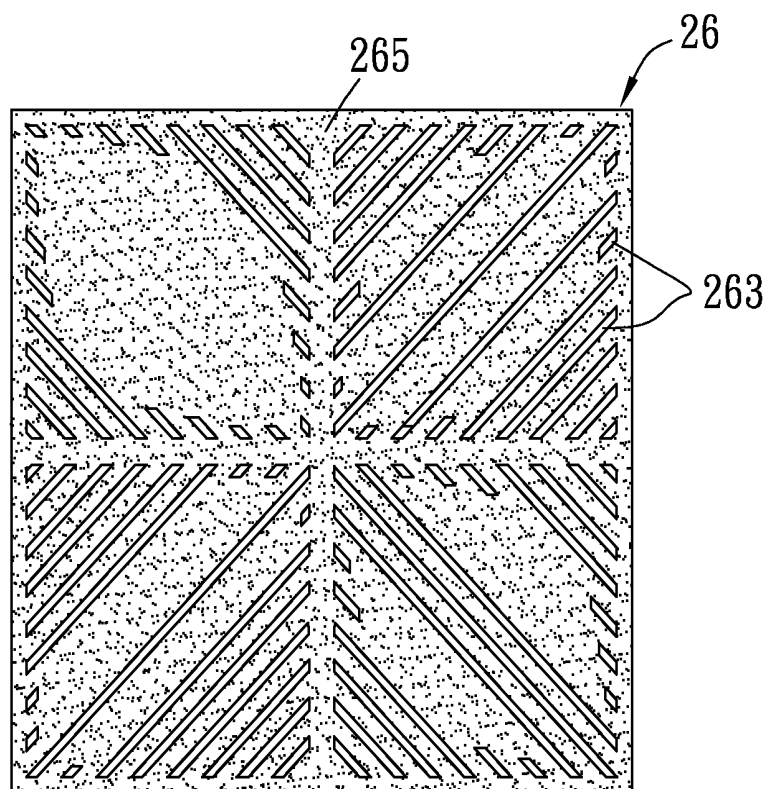


FIG. 12

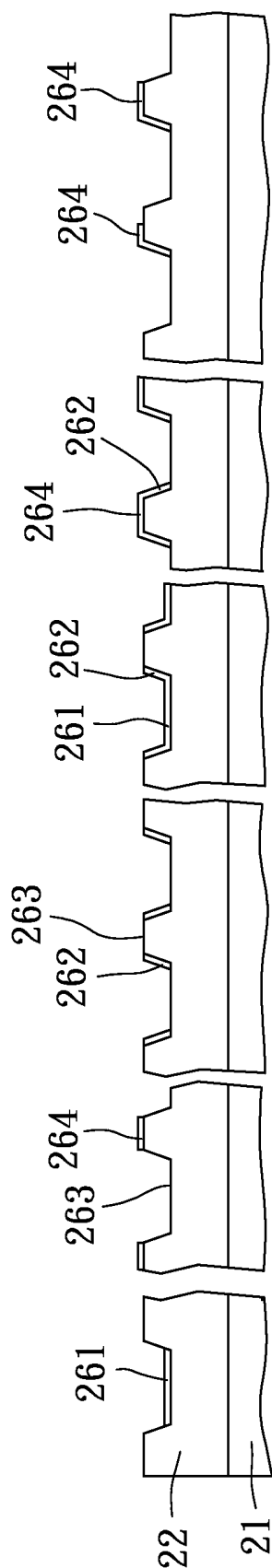


FIG. 13

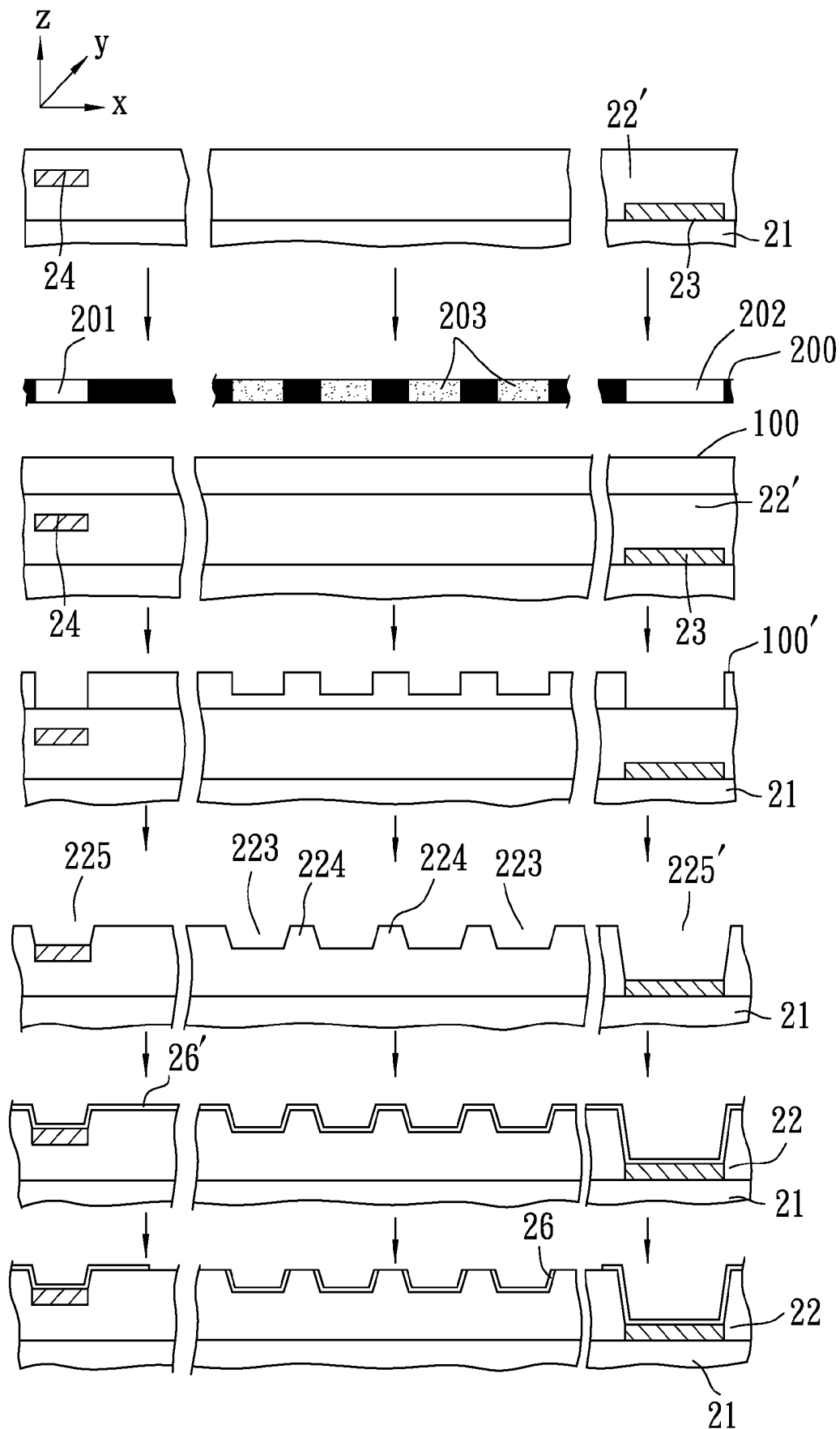


FIG. 14

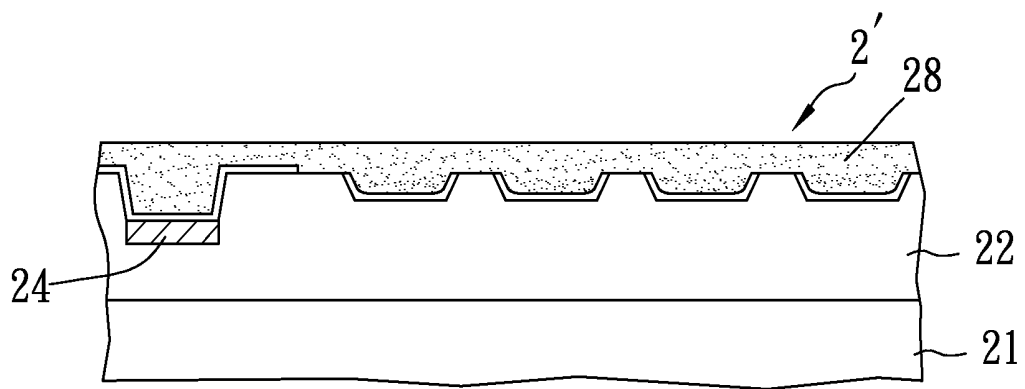


FIG. 15

LIQUID CRYSTAL DISPLAY DEVICE AND FABRICATION METHOD OF A CONDUCTIVE SUBSTRATE

CROSS-REFERENCE TO RELATED APPLICATION

This application claims priority of Taiwanese application no. 101109347, filed on Mar. 19, 2012.

BACKGROUND OF THE INVENTION

1. Field of the Invention

This invention relates to a liquid crystal device and a method for fabricating a conductive substrate, more particularly to a liquid crystal display device with alleviated dark region problem and a method for fabricating a conductive substrate applied to the liquid crystal display device.

2. Description of the Related Art

A conventional liquid crystal display device comprises: a first substrate having a first conductive layer; a second substrate having a second conductive layer; and a plurality of liquid crystal molecules disposed between the first and second substrates. The first substrate includes thin film transistors (TFTs), and is thus called a TFT side substrate. The second substrate includes a color filter, and is thus called a color filter side substrate. The first substrate includes: a transparent substrate; an insulator layer formed on a surface of the transparent substrate; a plurality of electrically isolated scan lines and data lines formed on the insulator layer; and the first conductive layer made of a transparent conductive material and formed on a surface of the insulator layer. The scan lines and the data lines cooperatively define a plurality of pixel areas. The first conductive layer is formed with a plurality of pixel electrodes that are formed in the pixel areas and that have a plurality of electrode slits. Each of the thin film transistors is electrically connected to the corresponding scan and data lines and the pixel electrodes. Because the structures and configurations of the first and second substrates are well known to a skilled artisan, a detailed description thereof is omitted herein for the sake of brevity.

When an external voltage is applied to the first and second substrates, the thin film transistors can be controlled through the scan and data lines so that the pixel electrodes and the second substrate cooperatively form an electric field, making longitudinal axes of the liquid crystal molecules tilt along a direction perpendicular to lines of electric force so as to generate color variation.

However, since there is no transparent conductive layer at the position of the electrode slits of the pixel electrodes, when an electric field is applied, electric field intensity of the pixel electrode is decreased at positions proximate to the electrode slits, thereby resulting in insufficient tilt for the liquid crystal molecules at the positions of the electrode slits in the pixel area. Therefore, dark regions are likely to be generated.

SUMMARY OF THE INVENTION

Therefore, an object of the present invention is to provide a liquid crystal display device with alleviated dark region problem on a periphery of a pixel area and on the boundaries of different domains.

Another object of the present invention is to provide a method for fabricating a conductive substrate for the liquid crystal display device.

According to one aspect of this invention, a liquid crystal display device comprises: a first substrate; a second substrate

spaced apart from the first substrate; and a plurality of liquid crystal molecules disposed between the first and second substrates.

The first substrate include: a transparent substrate, an insulator layer, and a pixel electrode.

The insulator layer is formed on a surface of the transparent substrate and is formed with a plurality of grooves. The pixel electrode is formed on a surface of the insulator layer and is formed with a plurality of electrode slits.

According to another aspect of this invention, a method for fabricating a conductive substrate for a thin film transistor liquid crystal display device comprises the following steps:

(a) preparing a substrate including a transparent substrate, an insulator layer formed on a surface of the transparent substrate, a plurality of spaced apart scan lines arranged in a first direction, and a plurality of spaced apart data lines arranged in a second direction transverse to the first direction, the scan lines being electrically isolated from the data lines, the insulator layer having a peripheral region;

(b) forming a photoresist layer on a surface of the insulator layer, preparing a gray-scale photomask that has a first pattern and a second pattern corresponding in position to a region of the insulator layer that is to be formed into via holes, and a plurality of third patterns corresponding in position to a region of the insulator layer that is to be formed into grooves, the first, second and third patterns having different transmittances, patterning the photoresist layer to remove the photoresist layer at a position corresponding to the first and second patterns until the insulator layer is exposed and parts of the photoresist layer at positions corresponding to the third patterns by photolithography so that the photoresist layer is formed into a mask pattern having different thicknesses;

(c) etching the insulator layer using the mask pattern as an etching mask so that the insulator layer is formed with a plurality of via holes corresponding in position to the first and second patterns, a plurality of spaced-apart grooves corresponding in position to the third patterns, and a plurality of isolated regions for isolating the grooves, the via holes having a depth different from that of the grooves; and

(d) forming a conductive layer made of a transparent conductive material on the etched insulator layer, removing a portion of the conductive layer by photolithography so that the conductive layer is formed into a pixel electrode that is formed with a plurality of electrode slits where the conductive layer is removed.

An effect of the present invention resides in that the insulator layer is formed with a plurality of grooves and simultaneously the pixel electrode is formed with a plurality of slits, so that the vertical electric field in the pixel area and the lateral electric field are raised. Accordingly, the orientation of the liquid crystal molecules can be effectively controlled so as to alleviate the dark-line problem of the liquid crystal display device.

BRIEF DESCRIPTION OF THE DRAWINGS

Other features and advantages of the present invention will become apparent in the following detailed description of the preferred embodiments of the invention, with reference to the accompanying drawings, in which:

FIG. 1 is a sectional diagram of the preferred embodiment of a liquid crystal display device according to this invention;

FIG. 2 is a top view of a first substrate of the preferred embodiment;

FIG. 3 is a schematic view showing a plurality of grooves in the preferred embodiment;

FIG. 4 is a schematic view showing another arrangement of the grooves in the preferred embodiment;

FIG. 5 is a schematic view showing still another arrangement of the grooves in the preferred embodiment;

FIG. 6 is a schematic view showing yet another arrangement of the grooves in the preferred embodiment;

FIG. 7 is a schematic view illustrating a first example of a pixel electrode in the preferred embodiment;

FIG. 8 is a schematic view illustrating a second example of the pixel electrode having a conductive frame portion in the preferred embodiment;

FIG. 9 is a schematic view showing a third example of the pixel electrode with four pattern regions;

FIG. 10 is a schematic view illustrating a fourth example of the pixel electrode;

FIG. 11 is a schematic view illustrating a fifth example of the pixel electrode;

FIG. 12 is a schematic view illustrating a sixth example of the pixel electrode;

FIG. 13 is a schematic diagram illustrating the distribution of first, second, and third electrode portions;

FIG. 14 shows consecutive steps of the preferred embodiment of a method for fabricating the first substrate according to this invention; and

FIG. 15 shows a schematic diagram illustrating the first substrate having a filler layer formed thereon.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENT

FIG. 1 is a schematic diagram of the preferred embodiment of a liquid crystal display device of this invention in a state prior to application of an electric field. FIG. 2 is a top view of a first substrate 2 of the preferred embodiment. The first substrate 2 in FIG. 1 is shown as a sectional diagram taken along line a-a in FIG. 2.

It is noted that in FIG. 1 a second direction (x) and a third direction (z) are transversely defined. In FIG. 2 a first direction (y) is defined to be transverse to the second and third directions (x), (z). In this way, the first, second and third directions (y), (x) and (z) are configured as a three-dimensional Cartesian coordinates system.

In the preferred embodiment of this invention, the liquid crystal display device comprises: a first substrate 2; a second substrate 3 that is spaced apart from the first substrate 2 and that forms an electric field with the first substrate 2 when a voltage is applied; and a plurality of liquid crystal molecules 4 that are disposed between the first and second substrates 2 and 3 approximately in the third direction (z) and that are likely to be tilted due to the generated electric field.

The first substrate 2 is a TFT side substrate and includes: a transparent substrate 21; an insulator layer 22; a plurality of scan lines 23; a plurality of data lines 24; a plurality of pixel areas 25; a plurality of pixel electrodes 26; and a plurality of thin film transistors (TFT) 27. Only part of the pixel areas 25 is shown in the figures of this invention.

The transparent substrate 21 is made of a transparent material, such as glass, quartz glass, polyacrylate, polyimide, or other transparent flexible materials. In this embodiment, the transparent substrate 21 is made of glass.

The insulator layer 22 is made of an insulated material and is formed on a surface of the transparent substrate 21.

Referring to FIG. 2, the scan and data lines 23, 24 are respectively arranged along the first direction (y) and the second direction (x) in the insulator layer 22 and are spaced apart from each other. The first and second directions (y) and (x) are mutually transverse and the scan and data lines 23, 24

are electrically isolated. The two adjacent scan lines 23 and the two adjacent data lines 24 cooperatively define a respective one of the pixel areas 25.

FIG. 3 is a top view of the insulator layer 22. Referring to FIGS. 1 to 3, the insulator layer 22 has a peripheral region 221, a central region 222 encircled by the peripheral region 221, a plurality of grooves 223 formed downwardly from a surface of the insulator layer 22 toward the substrate 21, a plurality of isolating regions 224 isolating the adjacent grooves 223, and a plurality of via holes 225 (see FIG. 1) for external electrical connection. Each of the grooves 223 has a bottom surface 226 and two lateral surfaces 227 connected to and extending upwardly from two opposite sides of the bottom surface 226.

It is noted that the grooves 223 should be designed to have an appropriate depth since a shallow depth is insufficient for providing adequate confinement for the liquid crystal molecules 4 and since an excessive depth would result in arrangement variation of the liquid crystal molecules 4 near a periphery of each of the grooves 223, thereby causing light leakage problem at the periphery of each of the grooves 223. Preferably, each of the grooves 223 has a depth ranging from 1500 Å to 3000 Å so as to provide adequate confinement and reduce light leakage. Moreover, the bottom surface 226 and each of the lateral surfaces 227 of each of the grooves 223 cooperatively define an angle (α). If the angle (α) is excessively large, a slow slope is formed such that electric field applied to the grooves 223 is insufficient to confine the liquid crystal molecules 4, thereby resulting in poor arrangement, while a right angle ($\alpha=90^\circ$) results in arrangement variation of the liquid crystal molecules 4 near a periphery of each of the grooves 223, thereby causing light leakage problem at the periphery of each of the grooves 223. Moreover, discontinuity problem between electrode portions formed in the grooves 223 is likely to occur in the pixel electrodes 26. Thus, the angle (α) between the bottom surface 226 and each of the lateral surfaces 227 of each of the grooves 223 is preferably larger than 90 degrees and up to 120 degrees.

The grooves 223 extend in a first extending direction (L1) that forms an acute angle (β) with the scan lines 23. The acute angle (β) ranges from 35 degrees to 55 degrees. In FIG. 3, the acute angle (β) is the angle between the first extending direction (L1) and the scan lines 23. Preferably, the acute angle (β) ranges from 40 degrees to 50 degrees. In this embodiment, the grooves 223 extend from the peripheral region 221 to the central region 222 in mirror symmetrical distribution as shown in FIG. 3, and the acute angle (β) between the extending direction (L1) of the grooves 223 and the scan lines 23 is 45 degrees. In other embodiments, the grooves 223 can be arranged in asymmetrical distribution depending on actual requirements.

Referring to FIGS. 4 to 6, the grooves 223 can also be designed in a pattern as shown in FIG. 4 or 5. That is, some of the grooves 223 formed in the peripheral region 221 extend toward the central region 222 so that some of the grooves 223 are in a continuous pattern (see FIG. 4), or the grooves 223 are only formed in the peripheral region, and are spaced apart from each other (see FIG. 5). The grooves 223 can be arranged in an asymmetrical distribution as shown in FIG. 6. Besides, it is further noted that the grooves 223 need not keep fixed distance from the scan lines 23 as long as the same do not extend beyond the pixel area 25. However, a fixed distance between the channel 223 and the scan lines 23 can be kept if required.

FIG. 7 is a top view of the pixel electrode 26. The pixel electrode 26 is formed in the pixel area 25 and defines a pattern region. Referring to FIGS. 1 and 7, the pixel electrode

26 has a plurality of first electrode portions 261 that are made of a transparent conductive material and that are formed on the bottom surface 226 of each of the grooves 223 (see FIG. 1), a plurality of second electrode portions 262 formed on the lateral surfaces 227, and a plurality of electrode slits 263 formed on top surfaces of the isolating regions 224. The electrode slits 263 can have a geometric shape, such as ellipse, square, rectangular, parallelogram, or trapezoid and can be distributed in an equidistant or a distance-increasing manner.

Preferably, the electrode slits 263 extend in a second extending direction (L2) that forms an acute angle (γ) with the scan lines 23. Each of the electrode slits 263 has a length along the second extending direction (L2) not shorter than 2 μm . The acute angle (γ) ranges from 35 degrees to 55 degrees. Preferably, the acute angle (γ) ranges from 40 degrees to 50 degrees. Preferably, the difference between the acute angle (γ) and the acute angle (β) is within ± 5 degree. Moreover, preferably, the sum (W_1) of a width of each of the first electrode portions 261 and a width of the adjacent one of the electrode slits 263 ranges from 4 μm to 8 μm . The ratio of the width of each of the first electrode portions 261 to the width of the adjacent one of the electrode slits 263 ranges from 0.5 to 2.

In this embodiment, the electrode slits 263 are parallelogram and are formed on top surfaces of the isolating regions 224 in the peripheral region 221. In FIG. 7, each of the electrode slits 263 has one end extending to a periphery of the pixel electrode 26, and the acute angle (γ) between the extending direction (L2) of the electrode slits 263 and the scan lines 23 is substantially 45 degrees.

Referring to FIG. 8, the pixel electrode 26 further has a conductive frame portion 265 surrounding the electrode slits 263 and disposed along the periphery of the pixel electrode 26. The end of each of the electrode slits 263 extends to the conductive frame portion 265. Interference in the liquid crystal molecules 4 arising from an electric field generated by the scan and data lines 23, 24 can be reduced by virtue of the conductive frame portion 265, thereby further reducing light leakage problem in dark state and peripheral regions in the pixel area 25. The conductive frame portion 265 has a width (W_d) ranging from 0.1 μm to 5 μm . More preferably, the conductive frame portion 265 has a width (W_d) ranging from 2 μm to 4 μm .

Referring to FIG. 9, it is noted that each of the pixel electrodes 26 further has at least one first branch 266 made of a transparent conductive material and extending along the second direction (x) to the conductive frame portion 265, and at least one second branch 267 intersecting the first branch 266 and extending along the first direction (y) to the conductive frame portion 265. In FIG. 9, one first branch 266 and one second branch 267 are used for illustration.

The first and second branches 266, 267, and the conductive frame portion 265 cooperatively define four pattern regions in the pixel electrode 26, so that the pixel electrode 26 has four domains. The electrode slits 263 are distributed in each of the pattern regions along the conductive frame portion 265, and the first and second branches 266, 267. Multi-domain orientation effect can be achieved by forming the pattern regions in the pixel electrode 26. Dark region problem in the periphery of the pixel area 25 can be further alleviated by the formation of the grooves 223, the electrode slits 263, and the first electrode portions 261 in the periphery of each of the pattern regions.

It is noted that the pattern regions are not easy to be defined when the widths of the first and second branches 266, 267 are insufficient, thereby likely resulting in poor arrangement of the liquid crystal molecules 4. However, the dark regions in

the pattern regions at the positions corresponding to the first and second branches 266, 267 become obvious when the first and second branches 266, 267 have excessive widths.

Preferably, the first and second branches 266 and 267 respectively have widths (W_1) and (W_2) ranging from 3 μm to 10 μm .

Referring to FIGS. 10 to 12, it is further noted that the electrode slits 263 disposed in different pattern regions can also be designed. Parts of the electrode slits 263 disposed on two adjacent lateral sides of each of the pattern regions extend inwardly from the conductive frame portion 265 so as to form certain continuous elongated electrode slits 263 (see FIG. 10), or all of the electrode slits 263 disposed on the two lateral sides of the pattern regions extend inwardly from the conductive frame portion 265 and are formed into a continuous and symmetrical pattern (see FIG. 11). The electrode slits 263 can be formed into an asymmetrical pattern as shown in FIG. 12.

Referring to FIG. 13, it is noted that the pixel electrodes 26 further have a plurality of third electrode portions 264 formed on a top surface of the isolating regions 224. The first, second, and third electrode portions 261, 262, and 264 can independently exist, simultaneously exist or selectively exist based on actual requirements. The third electrode portions 264 can completely or partially cover the top surface of the isolating regions 224. The electrode slits 263, in conjunction with the distribution pattern of the first, second, and third electrode portions 261, 262, and 264, can be simultaneously or respectively formed on the bottom surface 226 or the lateral surface 227 of each of the grooves 223 or the top surface of each of the isolating regions 224. FIG. 13 is a schematic diagram showing various situations of forming the first, second, and third electrode portions 261, 262, and 264 on the bottom surfaces 226 and the lateral surfaces 227 of the grooves 223 and the isolating regions 224.

The thin film transistors 27 are formed in the pixel areas 25. Each of the thin film transistors 27 is electrically connected to a corresponding one of the scan lines 23, a corresponding one of the data lines 24, and a corresponding one of the pixel electrodes 26.

The second substrate 3 is a color filter side substrate, and has a transparent second base substrate 31 and a transparent conductive layer 32 formed on a surface of the second base substrate 31 proximate to the liquid crystal molecules 4. The liquid crystal molecules 4 are made from a negative dielectric anisotropic liquid crystal material.

When external voltage is applied to the first and second substrates 2, 3, the thin film transistors 27 are controlled through the scan and data lines 23, 24 and the pixel electrodes 26 are thus driven by the external voltage. The pixel electrodes 26 and the transparent conductive layer 32 cooperate to form an electric field therebetween. Accordingly, longitudinal axis of each of the liquid crystal molecules 4 is tilted along a direction perpendicular to lines of electric force so as to generate brightness variation or color variation.

According to this invention, with the structural design of the first substrate 2, i.e., forming a plurality of the grooves 223 in the insulator layer 22, the pixel electrodes 26 can be formed with relatively large conductive areas. Thus, vertical electric field intensity in the grooves 223 in the pixel areas 25 is raised, tilt angle of the liquid crystal molecules 4 in the grooves 223 is increased, and dark region problem in the pixel areas 25 is alleviated. By virtue of the first electrode portion 261 or the second electrode portion 262, lateral electric field generated by the first or second electrode portion 261, 262 first passes the lateral surfaces 227. Accordingly, direction of the electric field passing through the lateral surfaces 227 can vary by adjusting the height and dielectric constant (ϵ) of the grooves

223 so as to reduce interference to the liquid crystal molecules **4**, that is caused by electric field at the periphery of the pixel electrode **26**, and further alleviate dark region problem in the periphery of the pixel areas **25**.

The structure of the aforesaid first substrate **2** in the preferred embodiment of this invention will become more apparent in the following description of a fabricating method thereof.

Referring to FIG. **14**, a method for fabricating the first substrate **2** comprises the following steps.

In step (a), a substrate is provided. The substrate includes a transparent substrate **21**, an un-etched insulator layer **22'** formed on a surface of the transparent substrate **21**, a plurality of spaced apart scan lines **23** arranged in a first direction (y), a plurality of spaced apart data lines **24** arranged in a second direction (x) transverse to the first direction (y), and a plurality of thin film transistors (not shown). The scan lines **23** are electrically isolated from the data lines **24**. The un-etched insulator layer **22'** has a peripheral region **221** and a central region **222** surrounded by the peripheral region **221**.

Since forming processes and materials for the substrate **21**, the un-etched insulator layer **22'**, the scan lines **23**, the data lines **24**, and the thin film transistors are well known to a skilled artisan and are not critical features of this invention, a detailed description thereof is omitted herein for the sake of brevity.

In step (b), a photoresist layer **100** is formed on a surface of the un-etched insulator layer **22'**, and a gray-scale photomask **200** is prepared. The gray-scale photomask **200** has a first pattern **201** and a second pattern **202** corresponding in position to a region of the un-etched insulator layer **22'** that is to be formed into via holes **225**, **225'**, and a plurality of third patterns **203** corresponding in position to a region of the insulator layer **22** that is to be formed into grooves **223**. The first, second and third patterns **201**, **202**, **203** may have different light transmittances. The photoresist layer **100** is subjected to a photolithography process using the gray-scale photomask **200** to remove the photoresist layer **100** at a position corresponding to the first and second patterns **201**, **202** until the un-etched insulator layer **22'** is exposed and a portion of the photoresist layer **100** at a position corresponding to the third pattern **203** is removed, so that the photoresist layer **100** is formed into a mask pattern **100'** with various thicknesses.

In detail, a photoresist material for the photoresist layer **100** used in step (b) can be a positive or negative photoresist material, and transmittances of the first, second, and third patterns **201**, **202**, and **203** of the gray-scale photomask **200** should be altered based on the photoresist material. In this embodiment, a positive photoresist is used as the photoresist material for illustration. In this embodiment, the first and second patterns **201**, **202** of the gray-scale photomask **200** are completely transparent, the third pattern **203** has transmittance smaller than those of the first and second patterns **201**, **202**, and the remaining parts are completely light-blocking. After the photoresist layer **100** is subjected to a photolithography process using the gray-scale photomask **200**, the photoresist material corresponding in position to the first and second patterns **201** and **202** can be completely removed and the un-etched insulator layer **22'** is thus exposed. Since the photoresist material corresponding in position to the third pattern **203** is subjected to relatively low exposure energy, the same would not be completely removed and some of the photoresist material would remain so that the photoresist layer **100** is formed into the mask pattern **100'** with various thicknesses.

It is noted that FIG. **14** includes schematic diagrams illustrating consecutive steps for forming the via holes **225**, **225'**

and the grooves **223** in three portions of the insulator layer **22** using the gray-scale photomask **200**. The leftmost and rightmost diagrams respectively illustrate a process for forming the via holes **225**, **225'** in the insulator layer **22** using the first and second patterns **201**, **202**. The middle diagrams illustrate a process for forming the grooves **223** in the insulator layer **22** using the third patterns **203**.

In step (c), the un-etched insulator layer **22'** is etched using the mask pattern **100'** as an etching mask so that the un-etched insulator layer **22'** is formed into a patterned insulator layer **22** formed with a plurality of via holes **225**, **225'** that correspond in position to the first and second patterns **201**, **202** and from which surfaces of the scan and data lines **23**, **24** are exposed, a plurality of spaced-apart grooves **223** corresponding in position to the third patterns **203**, and a plurality of isolated regions **224** for isolating the grooves **223**, thereby forming a semi-product.

In detail, the mask pattern **100'** is used as an etching mask in step (c). Dry or wet etching can be used to etch the un-etched insulator layer **22'** into patterned insulator layer **22**. Since the mask pattern **100'** on the insulator layer **22** has various thicknesses and thus has different shielding effects, the via holes **225**, **225'** and the grooves **223** having different thicknesses can be formed in the patterned insulator layer **22** using a single etching process. In this way, a further photomask process can be eliminated and manufacturing costs can be effectively reduced.

In step (d), a conductive layer **26'** made of a transparent conductive material is formed on the patterned insulator layer **22** of the semi-product. A portion of the conductive layer **26'** is removed by photolithography so as to form a plurality of electrode slits **263**. Therefore, a plurality of pixel electrodes **26** with predetermined patterns can be obtained, thereby obtaining the first substrate **2**.

It is noted that the method for fabricating the first substrate **2** further comprises a step (e) after step (d). In step (e), a filler layer **28** made of an insulating material is formed on the patterned insulator layer **22** and the pixel electrode **26**.

In detail, the step (e) is conducted by forming the filler layer **28** made of the insulator material such as silicon nitride, polymer resin, or silicon oxide, on the patterned insulator layer **22** and the pixel electrode **26** using chemical vapor deposition (CVD), sputtering, spin coating, or ink jet printing. In this embodiment, the filler layer **28** is formed on the patterned insulator layer **22** to obtain the first substrate **2'** as shown in FIG. **15**.

The filler layer **28** formed on a surface of the patterned insulator layer **22** cannot only provide a flat surface for subsequent processes, but also reduce light leakage problem in dark state. The light leakage problem is caused by change of orientation direction of the liquid crystal molecules **4** near the lateral surfaces **227** due to slope of the grooves **223**. Moreover, direction of the electric field passing through the filler layer **28** can be further adjusted by the thickness and dielectric constant (ϵ) of the filler layer **28**, thereby alleviating dark region problem in the periphery of the pixel areas **25**.

According to this invention, the first substrate **2** is designed with the grooves **223** and the electrode slits **263** on the periphery of each of the pixel areas **25** and with the first electrode portions **261** on the bottom surfaces **226** of the grooves **223**. By virtue of the structure of the grooves **223**, electric field direction in the first electrode portions **261** is modified so as to improve vertical electric field and increase lateral electrical field, thereby effectively alleviating dark region problem in the liquid crystal display device. Moreover, the grooves **223** and the isolating regions **224** of the first substrate **2** are formed using the gray-scale photomask **200** in a single photolithog-

raphy process rather than two photolithography processes used in the prior art. A photomask required in a second photolithography process can be omitted and manufacturing costs can be further reduced.

While the present invention has been described in connection with what are considered the most practical and preferred embodiments, it is understood that this invention is not limited to the disclosed embodiments but is intended to cover various arrangements included within the spirit and scope of the broadest interpretations and equivalent arrangements.

What is claimed is:

1. A method for fabricating a conductive substrate for a thin film transistor liquid crystal display device, comprising the following steps:

- (a) preparing a substrate including a transparent substrate, an insulator layer formed on a surface of the transparent substrate, a plurality of spaced apart scan lines arranged in a first direction, and a plurality of spaced apart data lines arranged in a second direction transverse to the first direction, the scan lines being electrically isolated from the data lines, the insulator layer having a peripheral region;
- (b) forming a photoresist layer on a surface of the insulator layer, preparing a gray-scale photomask that has a first pattern and a second pattern corresponding in position to a region of the insulator layer that is to be formed into via holes, and a plurality of third patterns corresponding in position to a region of the insulator layer that is to be formed into grooves, the first, second and third patterns having different transmittances, patterning the photoresist layer to remove the photoresist layer at a position corresponding to the first and second patterns until the insulator layer is exposed and parts of the photoresist layer at positions corresponding to the third patterns by

photolithography so that the photoresist layer is formed into a mask pattern having different thicknesses;

- (c) etching the insulator layer using the mask pattern as an etching mask so that the insulator layer is formed with a plurality of via holes corresponding in position to the first and second patterns, a plurality of spaced-apart grooves corresponding in position to the third patterns, and a plurality of isolated regions for isolating the grooves, the via holes having a depth different from that of the grooves; and
 - (d) forming a conductive layer made of a transparent conductive material on the etched insulator layer, removing a portion of the conductive layer by photolithography so that the conductive layer is formed into a pixel electrode that is formed with a plurality of electrode slits where the conductive layer is removed.
2. The method of claim 1, wherein each of the grooves formed in step (c) is defined by a bottom surface and two lateral surfaces connecting to and extending upwardly from two opposite sides of the bottom surface, the bottom surface and each of the lateral surfaces forming an acute angle ranging from 90 degrees to 120 degrees, the grooves having a depth ranging from 1500 Å to 3000 Å.
3. The method of claim 1, wherein the insulator layer further has a central region encircled by the peripheral region, the grooves formed in step (c) continuously or discontinuously extending from the peripheral region to the central region.
4. The method of claim 1, further comprising, after step (d),
- (e) forming a filler layer made of an insulator material on the etched insulator layer so that the filler layer fills and covers the grooves.

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摘要(译)

一种液晶显示装置,包括:第一基板;与第一基板间隔开的第二基板;多个液晶分子设置在第一和第二基板之间。第一基板包括透明基板,形成在透明基板的表面上并形成有多个凹槽的绝缘体层,以及形成在绝缘体层的表面上并形成有多个电极狭缝的像素电极。

